

**Monica Bollani**, (female) is a researcher of the Photonic and Nanotechnology Institute (IFN)-CNR in LNESS laboratory (Como, Italy). She graduated in chemistry, in 1997 at the Milano University (Italy), on self-assembled organic monolayer systems. She obtained a European PhD in November 2000 in materials physics from the University of Aix-Marseille (France), concerning microscopic and spectroscopic analysis of silicon sensors. She moved to a research post-doc position targeting the SiGe epitaxial growth at the ETH in Zurich (CH). In December 2004 she became a researcher at the IFN-CNR in Italy (Como) working in the optical and electron-beam lithography group in L-NESS, mainly dedicated to nanostructurization of low-dimensional semiconductor systems. She has a broad and multi-disciplinary education integrated by an extended experience in sensors fabrication, in photonics and plasmonic, project management and lab and clean room operations. Actually she is responsible of the nanofabrication activities in semiconductor materials in LNESS. To date she has 70 published articles and a chapter of a book.